

Charge collection and trapping effects in 75 μm , 100 μm and 150 μm thick n-type epitaxial silicon diodes after proton irradiation

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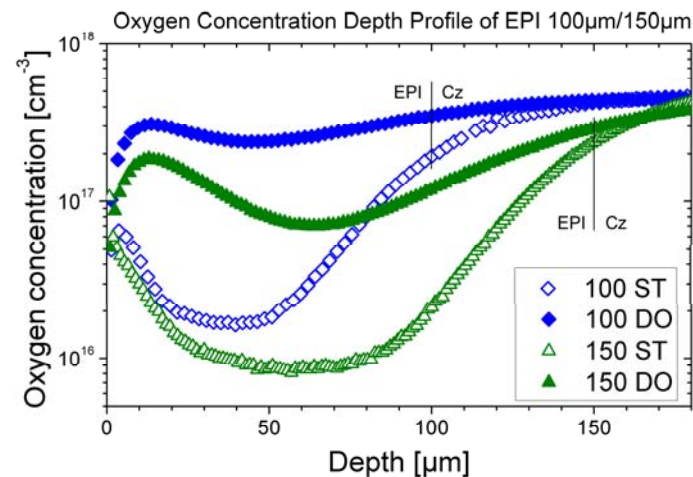
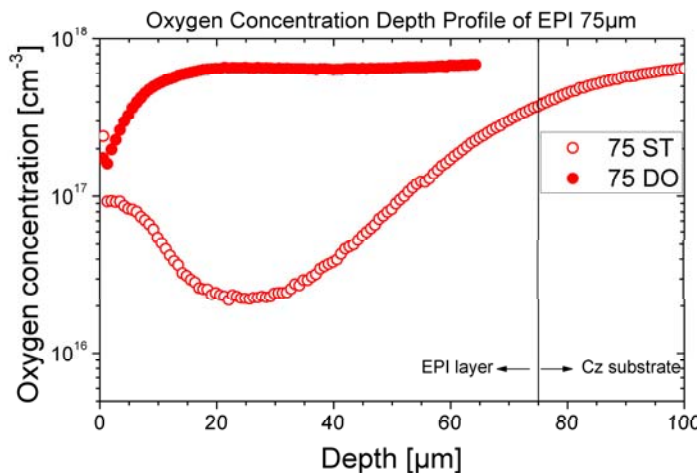




Overview on investigated diodes

- **Epitaxial** n-Si pad-detectors on Cz-substrate produced by ITME/CiS
- **Thickness:** 75 μm , 100 μm and 150 μm , **Size:** 5 x 5 mm^2 and 2.5 x 2.5 mm^2
- Standard (**ST**) and oxygen enriched (**DO**, diffusion for 24h at 1100°C) material
- **24 GeV/c-proton-irradiation** (CERN PS), $\Phi_{\text{eq}} = 1 \times 10^{14} - 1 \times 10^{16} \text{ cm}^{-2}$

Material	d [μm]	Wafer	Orientation	$N_{\text{eff},0}$ [P] [10^{12} cm^{-3}]	[O] [10^{16} cm^{-3}]
EPI-ST 75	74	8364-03	<111>	26	9.3
EPI-DO 75	72	8364-07	<111>	26	60.0
EPI-ST 100	102	261636-05	<100>	15	5.4
EPI-DO 100	99	261636-01	<100>	15	28.0
EPI-ST 150	147	261636-13	<100>	8.8	4.5
EPI-DO 150	152	261636-09	<100>	8	14.0



TCT with 670 nm laser light

- Problem so far: determination of τ_{eff} via Charge Correction Method requires time-resolved signal
BUT: $t_c \approx$ rise time of the signal (few ns)

- Example: **OLD SETUP**

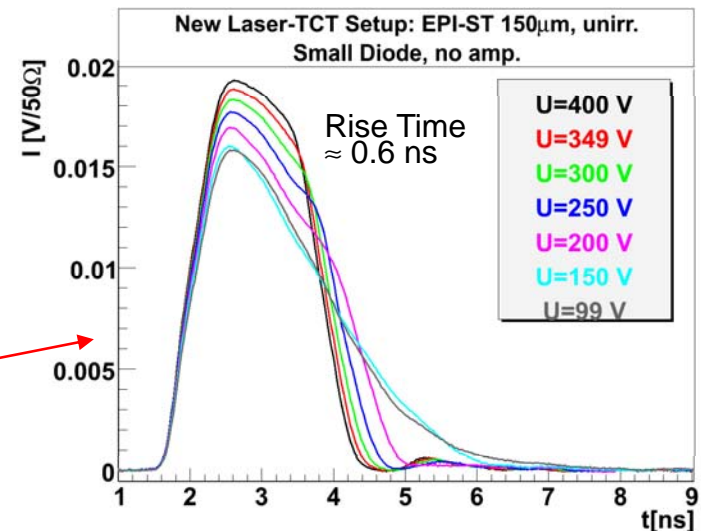
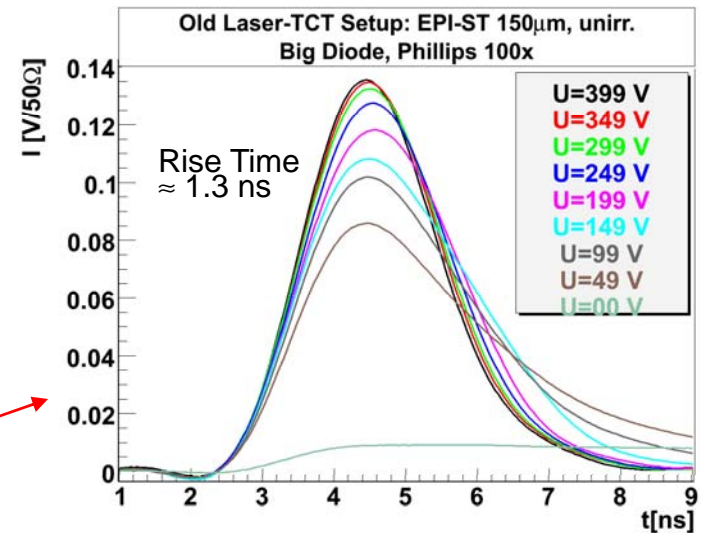
- laser pulse ≈ 1 ns
- 500 MHz oscilloscope \rightarrow 680 ps rise time
- only 5×5 mm² diodes mountable
 $\rightarrow \tau_{\text{RC}} \approx 880$ ps for 150 μm

\Rightarrow no time-resolved signal

- Solution: **NEW SETUP**

- 70 ps laser pulse
- 2.5×2.5 mm² diodes mountable
 $\rightarrow \tau_{\text{RC}} \approx 225$ ps for 150 μm
- new 2.5 GHz oscilloscope \rightarrow 136 ps rise time

\Rightarrow time-resolved signal for 150 μm



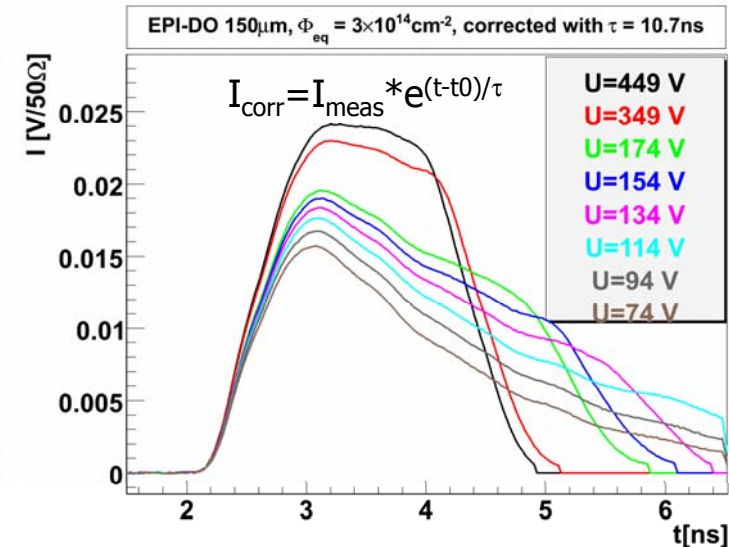
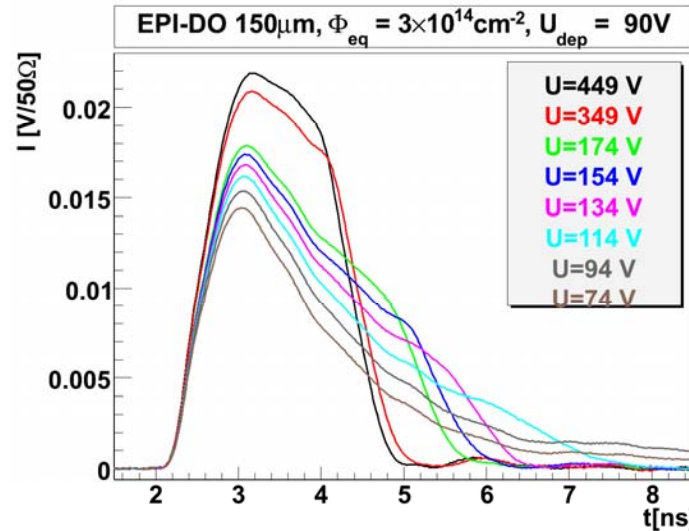
TCT electron current signal examples

as measured :

corrected:

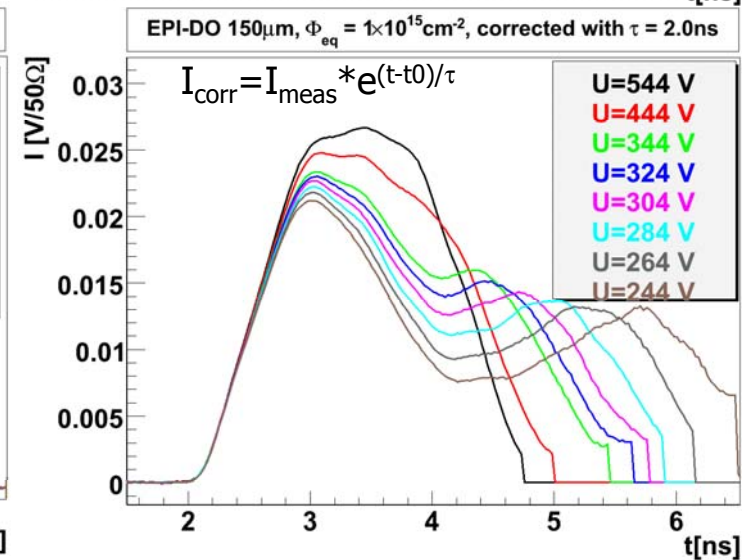
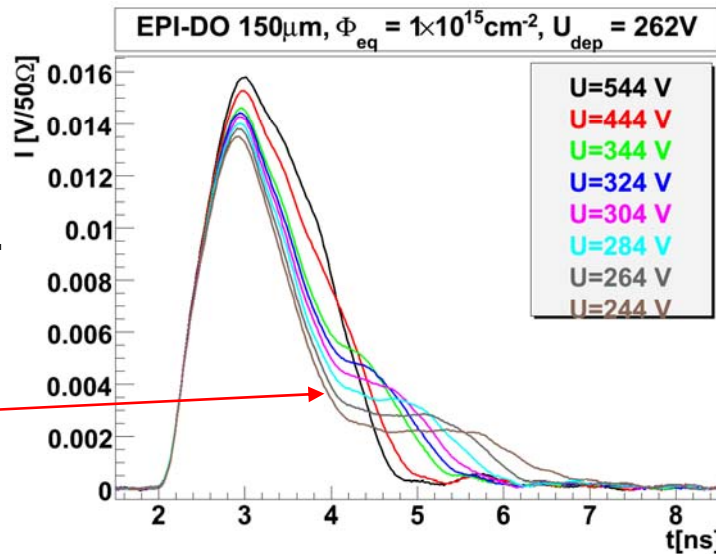
EPI-DO 150 μm
 $\Phi_{\text{eq}} = 3 \times 10^{14} \text{ cm}^{-2}$
 30 min at 80°C
 meas. at room temp.

No type inversion
 (confirms conclusions from
 annealing curve)



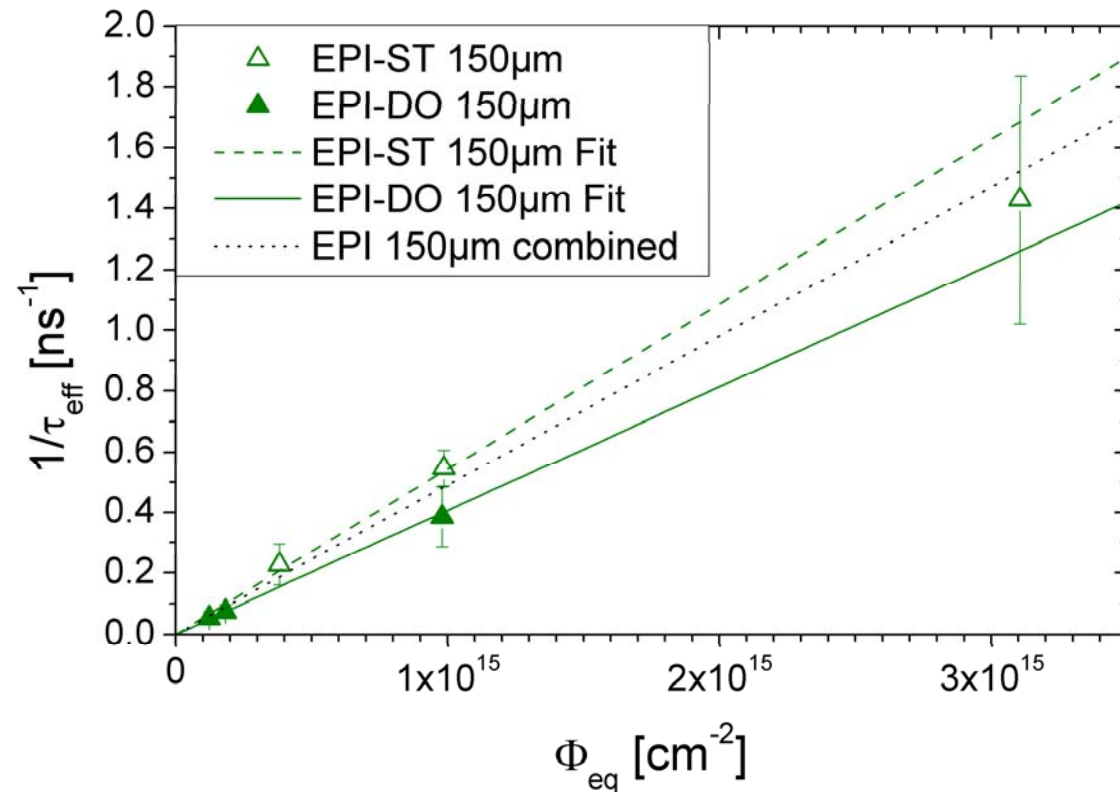
EPI-DO 150 μm
 $\Phi_{\text{eq}} = 1 \times 10^{15} \text{ cm}^{-2}$
 30 min at 80°C
 meas. at room temp.

Double Junction!



Trapping time constant

- **Charge Correction Method** after deconvolution and cutoff
- Resulting τ_{eff} sensitive on cutoff level, integration window, fitting range
→ quite large **uncertainty** (15 - 40%)
- Result: Trapping probability $1/\tau_{\text{eff}}$ **fluence-proportional**
- **Damage parameter β_e** in the same range as value for FZ*
- 25% difference between ST and DO, but due to large errors not significant

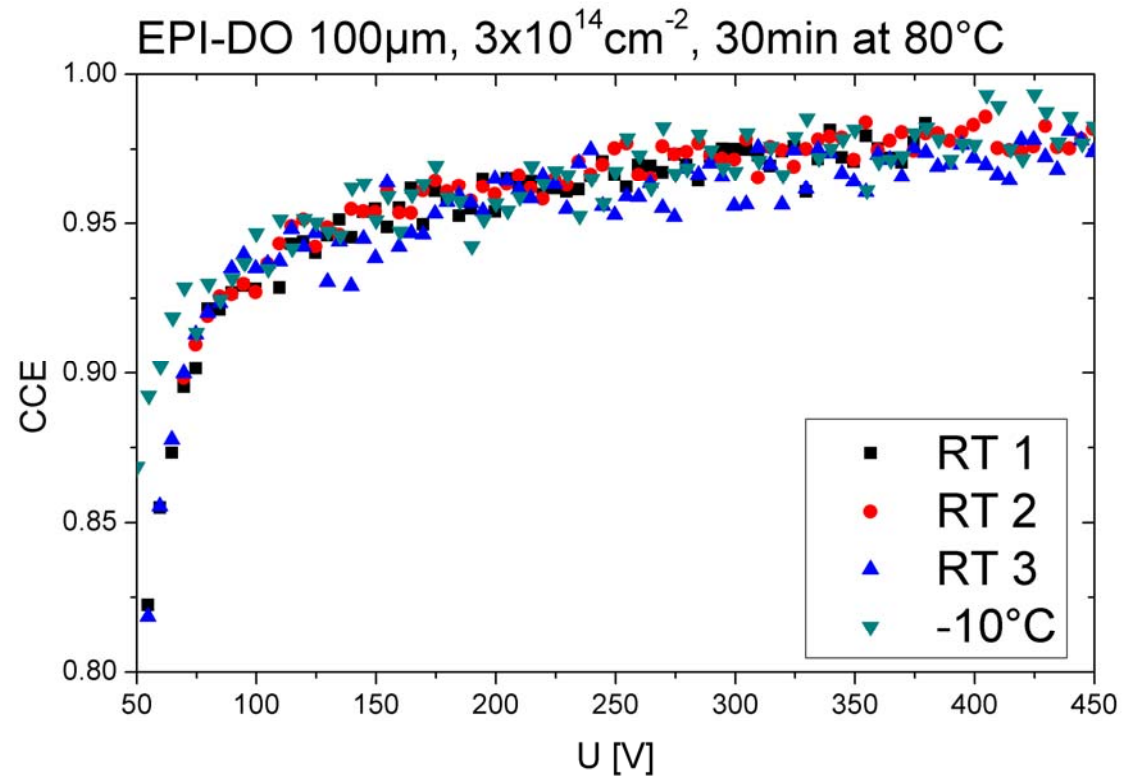


	$\beta_e [10^{-16} \text{ cm}^2 \text{ ns}^{-1}]$
EPI-ST	5.4 ± 0.5
EPI-DO	4.0 ± 0.7
EPI comb.	4.9 ± 0.4
cf. FZ*	5.1

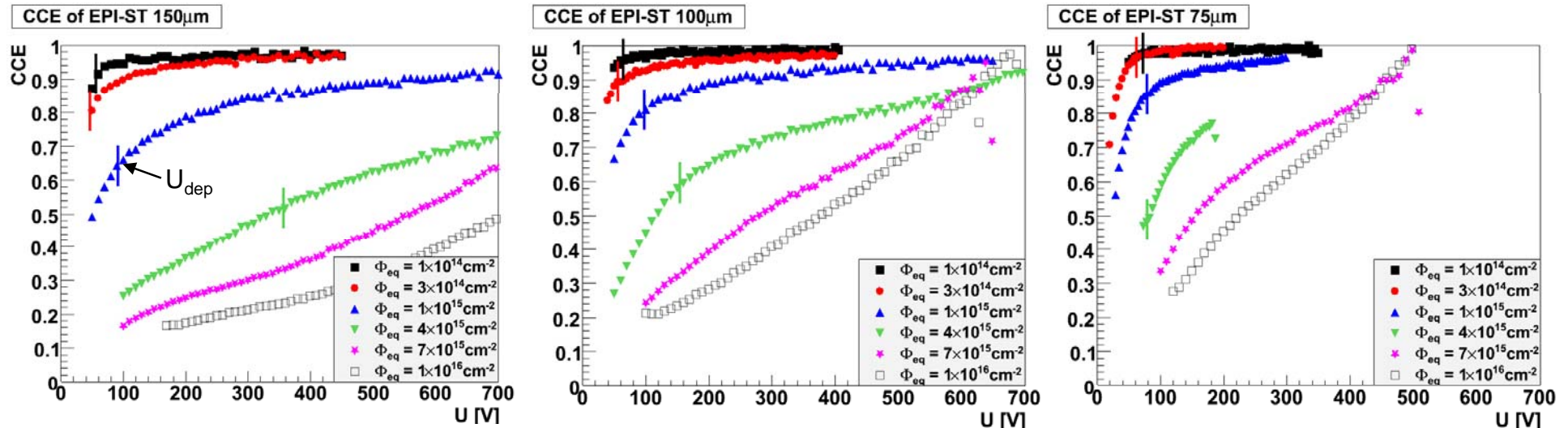
*see G.Kramberger's Doctoral Thesis, for T=294K

TCT with 5.8 MeV α -particles

- ^{244}Cm α -source: 5.8 MeV, 26 μm penetration depth (SRIM)
- CCE obtained by normalising integrated charge to the one of unirradiated diode
- Measurements usually at RT, but for highly irradiated diodes at -10°C because of high currents
- Good reproducibility, no difference for CCE between RT and -10°C
→ mobility rise and τ_{eff} decrease at low T obviously compensate

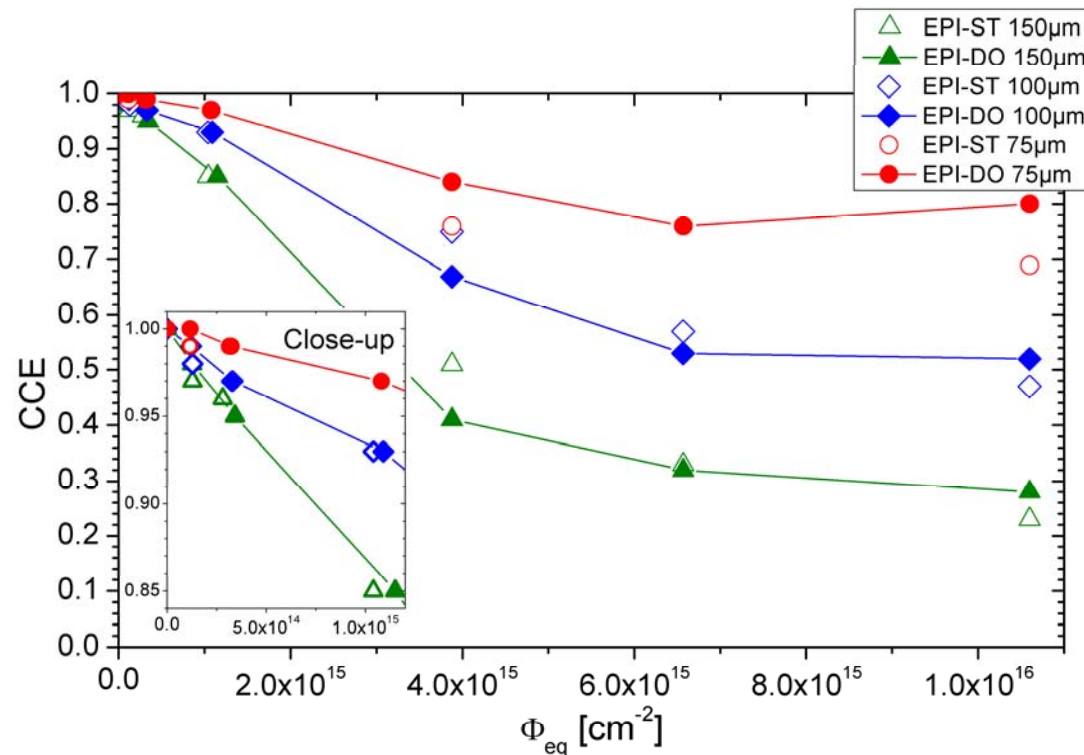


CCE as a function of bias



- CCE(U) almost saturating for low fluences
- CCE(U) rises strongly for high fluences (exceeds even 1 at high U for thin diodes) → **avalanche** effects?
- CCE degrades with fluence

CCE as a function of fluence (at 350V)



- CCE **degrades with fluence**, but deceleration at high fluences due to avalanche effects?
- CCE **improves for decreasing thickness** as t_c decreases (smaller distance, higher field)
- No significant difference between ST and DO

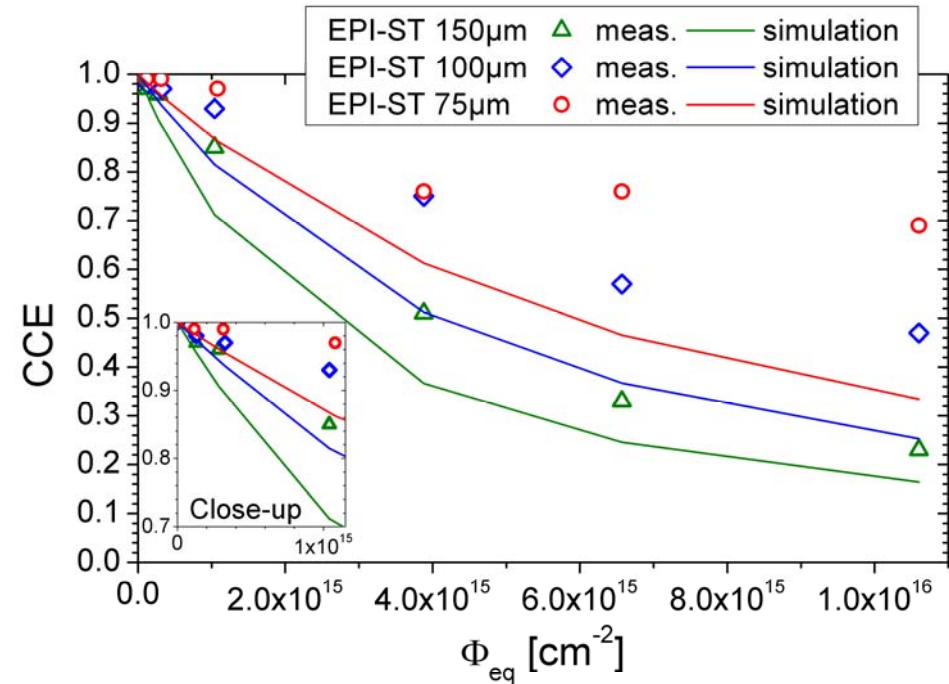
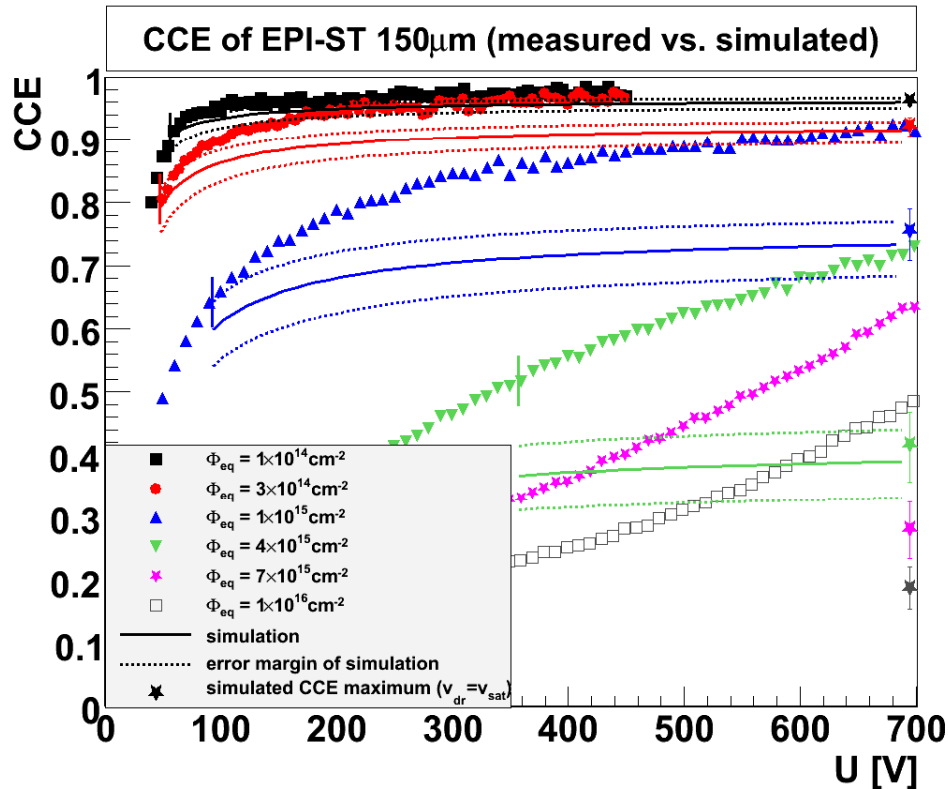
Simulation of CCE

- τ_{eff} found to be linear with fluence, same values as in FZ
→ everything as expected and understood?
→ **check with simulation!**
- Simulation of CCE with α -particles taking τ_{eff} obtained by CCM
- Input:
 - v_{dr} parameterisation including saturation
 - linear electric-field approximation (reasonable for $U \gg U_{\text{dep}}$)
 - e-h pair distribution after penetration of α -particles as calculated by SRIM
 - $\beta_e = 5.1 \times 10^{-16} \text{ cm}^2 \text{ ns}^{-1}$, $\beta_h = 6.5 \times 10^{-16} \text{ cm}^2 \text{ ns}^{-1}$ used for calculating τ_{eff} (G. Kramberger)

CCE measured vs. simulated

CCE(U):

CCE(Φ_{eq}) at 350V:



- **No good agreement:** simulation systematically underestimate measurements
 - Avalanche effects? But should not be the case for lowest fluences
 - Plasma effect? But same problem seen before for laser- and β -TCT (see e.g. G.Kramberger, 8th RD50 Workshop Prague; L.Beattie NIM A 421 (1999), 502)
 - Model assumptions (e.g. $v_{dr}(E)$, $E(x)$) wrong?
But even calculated maximum CCE in case of assuming $v_{dr} = v_{sat}$ everywhere is too low!
- **Discrepancy must be related to trapping model**

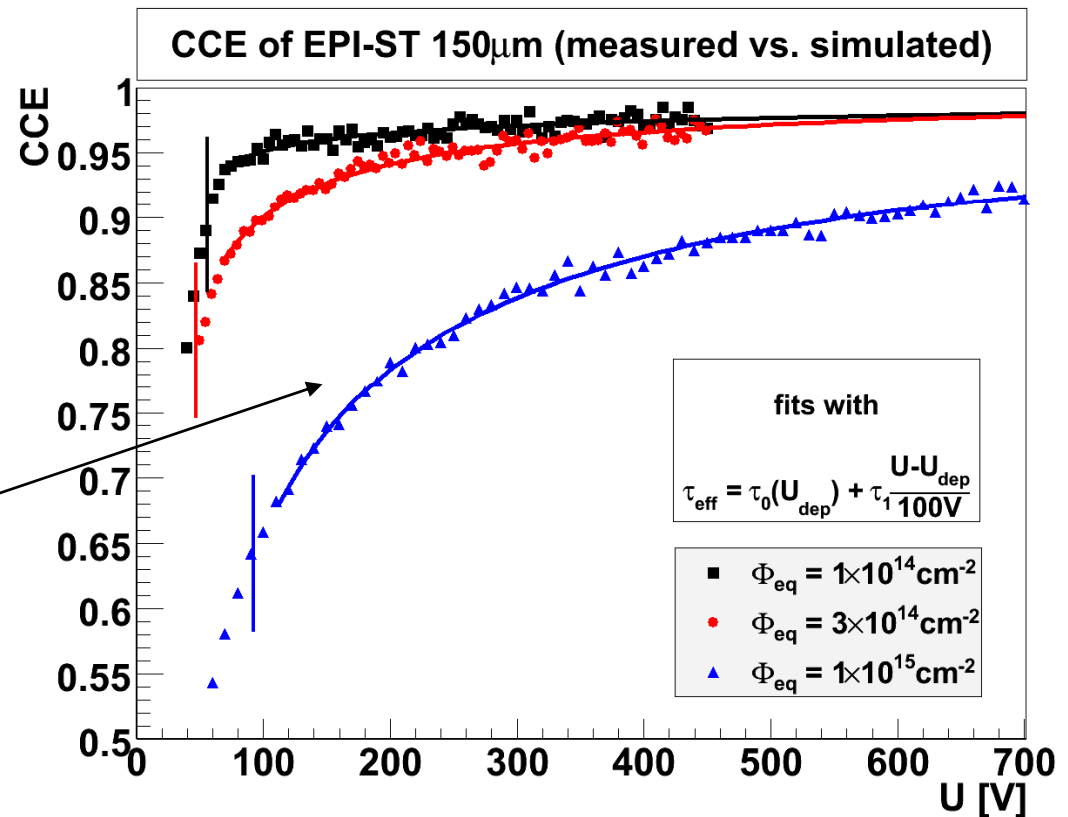
Possible solutions (speculative!)

- Fast detrapping?
- Exponential decay $\exp(-t/\tau_{\text{eff}})$ with constant τ_{eff} does not provide accurate description of trapping?

- assumption $v_{\text{dr}} \ll v_{\text{th}}$ not valid if $v_{\text{dr}} \approx v_{\text{sat}}$?
- cross section dependent on v_{dr} ?
- inhomogeneous trap density?
- trap filling at high currents?

- First try:
voltage-dependent τ_{eff}^*
→ fits CCE(U) well!
→ modified CCM can also produce flat slope of $Q(U)$!

*cf. L.Beattie NIM A 421 (1999), 502



Summary

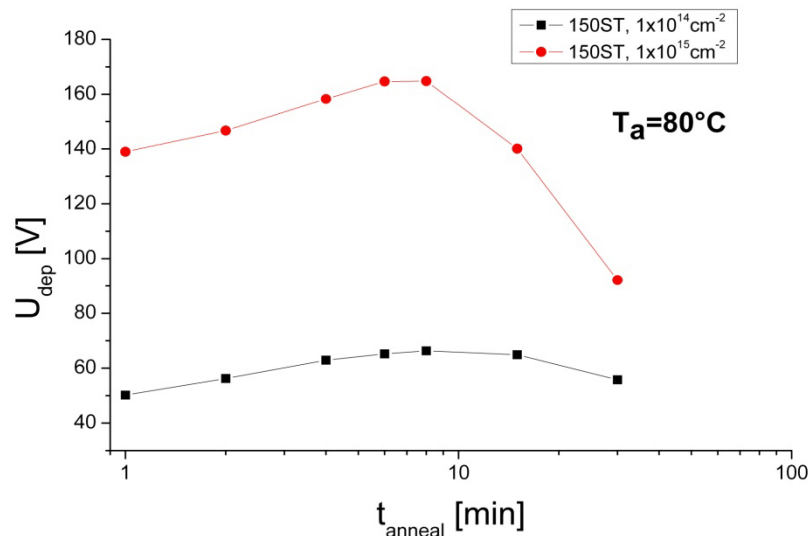
- New Laser-TCT setup with improved rise time
 - Time-resolved signal even for 150 μm EPI diodes
 - No type inversion in p-irradiated n-type EPI diodes
 - Double Junction at high fluences
 - CCM possible: $1/\tau_{\text{eff}}$ linear with fluence with β_e similar to FZ
- CCE with α -particles:
 - CCE increases for decreasing thickness
 - No difference between ST and DO
 - Degradation with fluence decelerated due to avalanche effects
- Simulated CCE underestimates measurements
 - Modified trapping description needed?
 - E.g. voltage-dependent τ_{eff} fits data well

BACKUP SLIDES

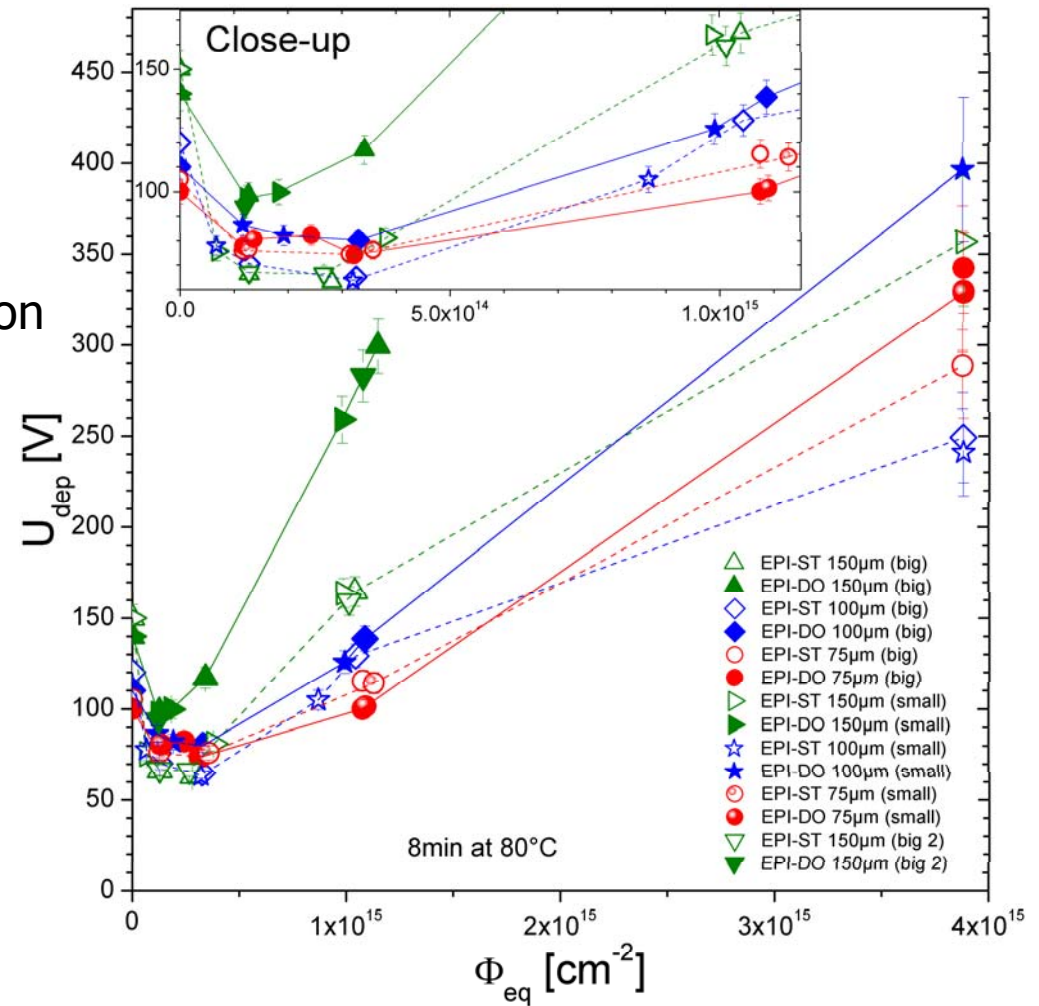
Depletion Voltage (from CV at 10 kHz)

- **CV/IV** measurable up to $4 \times 10^{15} \text{ cm}^{-2}$ at room temperature
- **Annealing** curve at 80°C (isothermal) \rightarrow no type inversion
- **Stable Damage** (8 min at 80°C): first donor removal, then donor introduction with $g_c(\text{DO}) > g_c(\text{ST})$

Annealing curve:

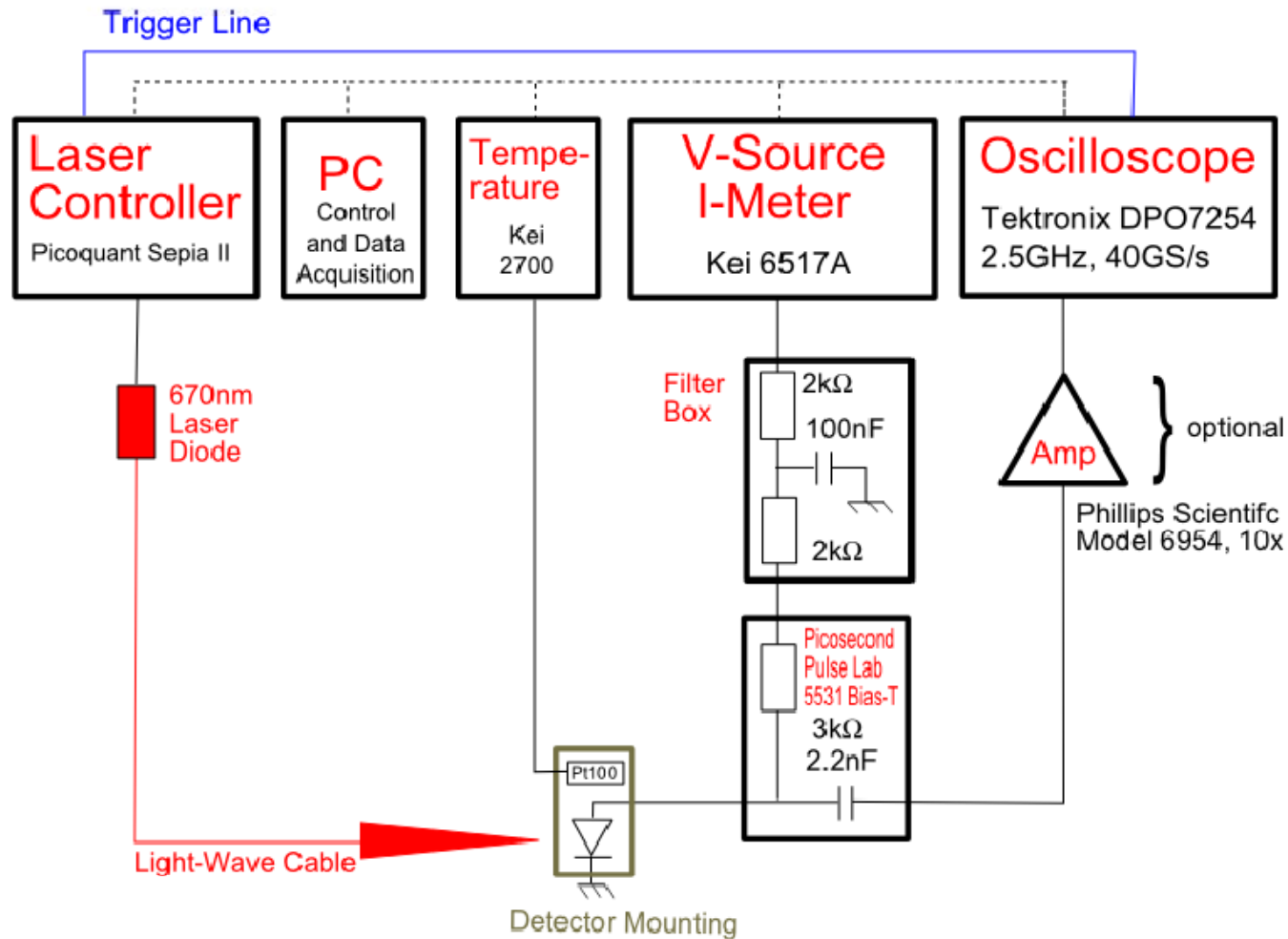


Stable Damage:

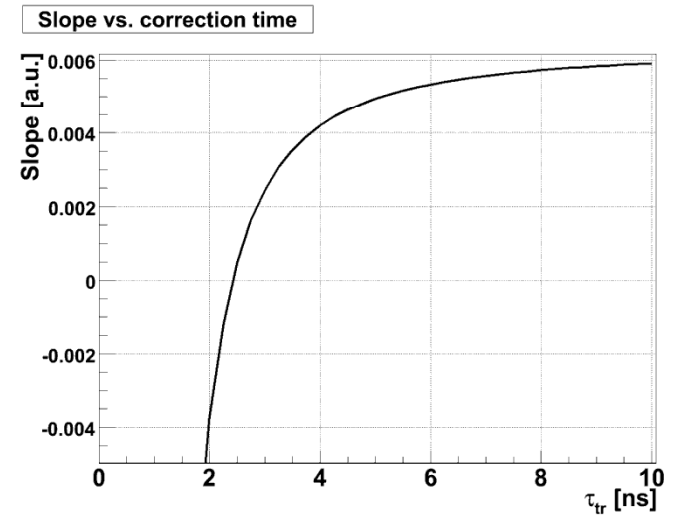
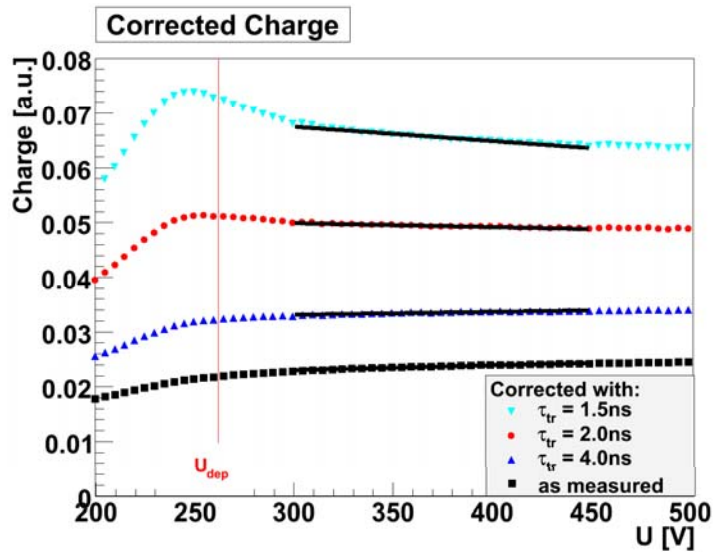
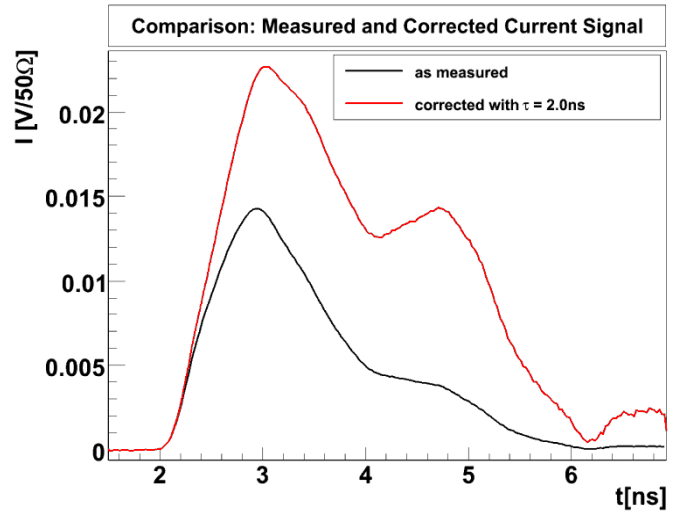


New Laser-TCT Setup

Laser -TCT Setup

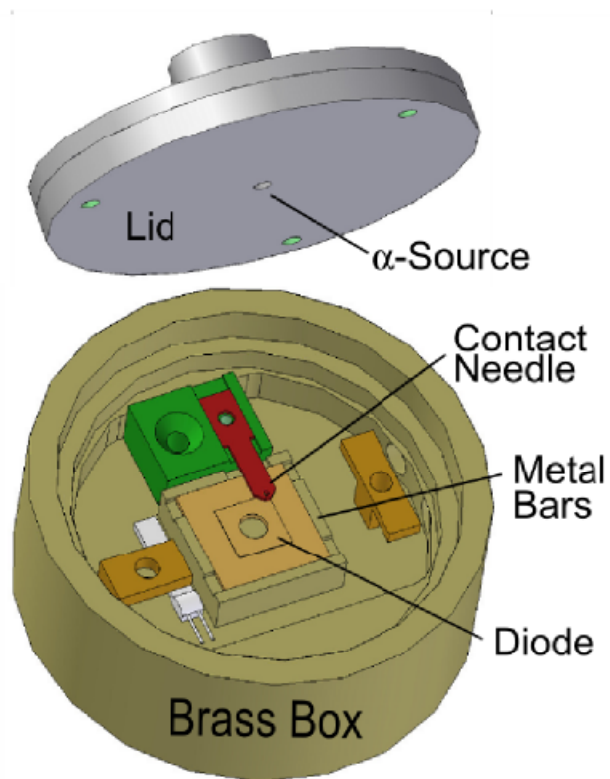


CCM

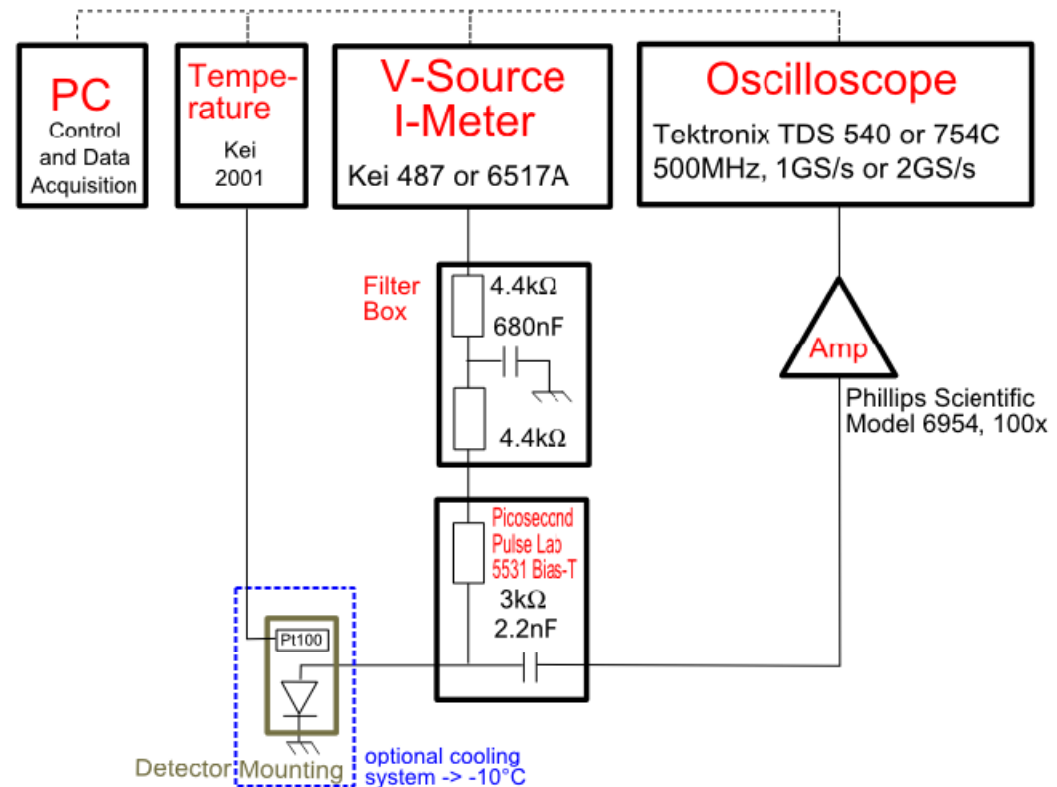


Alpha-TCT Setup

Detector Mounting



α -TCT Setup



Simulation details

Integrated induced charge for e-h pair deposited at x_0 (e + h contribution):

$$Q_{x_0} = \frac{Q_{0,x_0}}{d} \left[\int_{x_0}^d \exp\left(-\frac{t(x)}{\tau_{eff,e}}\right) dx - \int_{x_0}^0 \exp\left(-\frac{t(x)}{\tau_{eff,h}}\right) dx \right] \quad \text{with} \quad t(x) = \int_{x_0}^x \frac{1}{v_{dr}(E(x'))} dx'$$

Drift velocity parameterisation (C.Jacobini, Sol.State El., Vol. 20, 1977):

$$v_{dr} = \frac{\mu_0 E}{\left(1 + \left(\frac{\mu_0 E}{v_{sat}}\right)^\beta\right)^{1/\beta}} \quad \text{with}$$

$\mu_{0,e}$	$= 1.51 \times 10^9 \cdot T^{-2.42} \frac{cm^2}{Vs}$	\Rightarrow	$1605.4 \frac{cm^2}{Vs}$	at 294K
$v_{sat,e}$	$= 1.53 \times 10^9 \cdot T^{-0.87} \frac{cm}{s}$	\Rightarrow	$1.09 \times 10^7 \frac{cm}{s}$	
β_e	$= 2.57 \times 10^{-2} \cdot T^{0.66}$	\Rightarrow	1.09	
$\mu_{0,h}$	$= 1.31 \times 10^8 \cdot T^{-2.2} \frac{cm^2}{Vs}$	\Rightarrow	$486.3 \frac{cm^2}{Vs}$	
$v_{sat,h}$	$= 1.62 \times 10^8 \cdot T^{-0.52} \frac{cm}{s}$	\Rightarrow	$0.84 \times 10^7 \frac{cm}{s}$	
β_h	$= 0.46 \cdot T^{0.17}$	\Rightarrow	1.21	

Linear electric-field approximation:

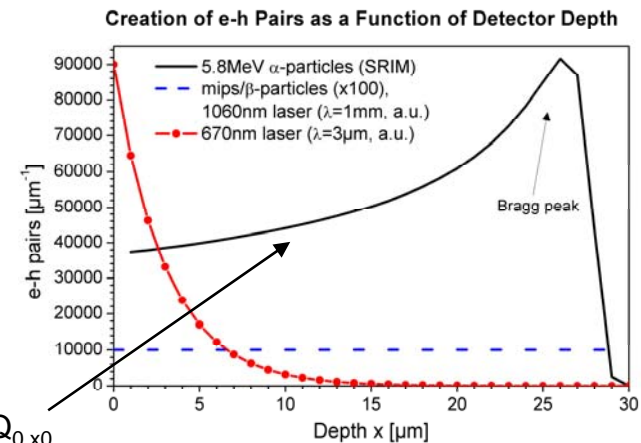
$$E(x) = \frac{1}{d} \left[U_{dep} \left(\frac{2x}{d} - 1 \right) - U \right], \quad U \geq U_{dep}$$

Integration over all positions

where e-h pairs were created:

$$Q_{total} = \int_0^d Q_{x_0} dx_0$$

Charge deposition as a function of detector depth Q_{0,x_0} calculated by SRIM for 5.8 MeV α -particles



Results from U-dependent τ_{eff} fit of CCE(U)

$$\tau_{\text{eff},e} = \tau_0(U_{\text{dep}}) + \tau_1 \frac{(U - U_{\text{dep}})}{100V}$$

$\tau_0(U_{\text{dep}}) = 22.5ns,$	$\tau_1 = 2.0ns$	for $1 \times 10^{14}cm^{-2}$
$\tau_0(U_{\text{dep}}) = 8.9ns,$	$\tau_1 = 4.0ns$	for $3 \times 10^{14}cm^{-2}$
$\tau_0(U_{\text{dep}}) = 2.4ns,$	$\tau_1 = 1.0ns$	for $1 \times 10^{15}cm^{-2}$